

<b>Notice of References Cited</b>	Application/Control No. 10/043,027	Applicant(s)/Patent Under Reexamination CHUNG ET AL.	
	Examiner William C. Vesperman	Art Unit 2813	Page 1 of 1

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	C	US-2002/0100959	08-2002	Joo et al.	257/532
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**NON-PATENT DOCUMENTS**

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	U	Handbook of Chemical Vapor Deposition (CVD), Noyes Publications, Copyright 1992, Author : Hugh O. Pierson, Pages 234, Section 5.6
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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